

| L Number | Hits | Search Text | DB | Time stamp |
|----------|------|---------------------------------------------------------------------------|-------|------------------|
| 1 | 1 | ("6281146").PN. | USPAT | 2004/06/24 10:59 |
| 5 | 1 | ("6579811").PN. | USPAT | 2004/06/24 11:48 |
| 6 | 0 | ((("6579811").PN.) and nitrogen | USPAT | 2004/06/24 11:48 |
| - | 1 | ("6579811").PN. | USPAT | 2004/06/24 11:48 |
| - | 500 | (438/758).CCLS. | USPAT | 2004/06/23 16:12 |
| - | 139 | ((438/758).CCLS.) and wafer and nitrogen and chamber | USPAT | 2004/06/23 16:13 |
| - | 88 | ((438/758).CCLS.) and wafer and nitrogen and chamber and plasma | USPAT | 2004/06/23 16:13 |
| - | 133 | (257/9).CCLS. | USPAT | 2004/06/23 16:13 |
| - | 8 | ((257/9).CCLS.) and plasma and chamber and wafer | USPAT | 2004/06/23 16:14 |
| - | 0 | ((257/9).CCLS.) and plasma and chamber and wafer and nitrogen and ammonia | USPAT | 2004/06/23 16:14 |
| - | 6 | ((257/9).CCLS.) and plasma and chamber and wafer and nitrogen | USPAT | 2004/06/23 16:14 |

| L Number | Hits | Search Text | DB | Time stamp |
|----------|------|-------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------|-------|------------------|
| - | 0 | (plasma adj enhanced) and CVD and apparatus and chamber and dome and insulator and gas and ring and susceptor and heater and wafer and sidewall and pump | USPAT | 2004/03/31 10:28 |
| - | 0 | PECVD and apparatus and chamber and dome and insulator and gas and ring and susceptor and heater and wafer and sidewall and pump | USPAT | 2004/03/31 10:28 |
| - | 2 | PECVD and apparatus and chamber and dome and insulator and gas and ring and susceptor and heater and wafer and sidewall and pump | USPAT | 2004/03/31 10:32 |
| - | 974 | PECVD and apparatus and chamber and d insulator and gas and ring and susceptor and heater and wafer and sidewall and pump | USPAT | 2004/03/31 10:32 |
| - | 964 | PECVD and apparatus and chamber and d insulator and gas and ring and susceptor and heater and wafer and sidewall and pump and (power adj source) and upper | USPAT | 2004/03/31 10:32 |
| - | 915 | PECVD and apparatus and chamber and d insulator and gas and ring and susceptor and heater and wafer and sidewall and pump and (power adj source) and upper and nozzle and steel | USPAT | 2004/03/31 15:44 |
| - | 4 | PECVD and apparatus and chamber and insulator and gas and ring and susceptor and heater and wafer and sidewall and pump and (power adj source) and upper and nozzle and steel and (vacuum adj pump) | USPAT | 2004/03/31 15:31 |
| - | 0 | PECVD and apparatus and (upper adj chamber) and (lower adj chamber) and insulator and gas and ring and susceptor and heater and wafer and sidewall and pump and (power adj source) and nozzle and steel and (vacuum adj pump) | USPAT | 2004/03/31 12:54 |
| - | 0 | PECVD and apparatus and (upper adj chamber) and (lower adj chamber) and insulator and gas and ring and susceptor and heater and wafer and sidewall and pump and (power adj source) and nozzle | USPAT | 2004/03/31 12:55 |
| - | 0 | PECVD and apparatus and (upper adj chamber) and insulator and gas and ring and susceptor and heater and wafer and sidewall and pump and (power adj source) and nozzle | USPAT | 2004/03/31 14:20 |
| - | 2 | PECVD and apparatus and dome and insulator and gas and ring and susceptor and heater and wafer and sidewall and pump and (power adj source) and nozzle | USPAT | 2004/03/31 15:31 |
| - | 0 | PECVD and apparatus and dome and insulator and gas and ring and susceptor and heater and wafer and sidewall and pump and (power adj source) and nozzle and "57" | USPAT | 2004/03/31 14:55 |
| - | 0 | PECVD and apparatus and dome and insulator and gas and ring and susceptor and heater and wafer and sidewall and pump and (power adj source) and nozzle and steel | USPAT | 2004/03/31 15:31 |
| - | 4 | PECVD and apparatus and chamber and insulator and gas and ring and susceptor and heater and wafer and sidewall and pump and (power adj source) and upper and nozzle and steel and (vacuum adj pump) and steel | USPAT | 2004/03/31 15:36 |
| - | 4 | PECVD and apparatus and chamber and insulator and gas and ring and susceptor and heater and wafer and sidewall and nozzle and (stainless adj steel) | USPAT | 2004/03/31 15:37 |
| - | 4 | PECVD and apparatus and chamber and insulator and (gas with ring) and susceptor and heater and wafer and sidewall and nozzle and (stainless adj steel) | USPAT | 2004/03/31 15:44 |
| - | 0 | PECVD and apparatus and chamber and insulator and (gas with ring) and susceptor and heater and wafer and sidewall and nozzle and (stainless adj steel) and (loadlock adj chamber) | USPAT | 2004/03/31 15:44 |
| - | 911 | PECVD and apparatus and chamber and d insulator and gas and ring and susceptor and heater and wafer and sidewall and pump and (power adj source) and upper and nozzle and steel and (loadlock adj chamber) | USPAT | 2004/03/31 15:45 |
| - | 0 | PECVD and apparatus and chamber and insulator and gas and ring and susceptor and heater and wafer and sidewall and pump and (power adj source) and upper and nozzle and (stainless adj steel) and (loadlock adj chamber) | USPAT | 2004/03/31 15:45 |
| - | 0 | PECVD and apparatus and chamber and insulator and (gas with ring) and susceptor and heater and wafer and sidewall and pump and (power adj source) and nozzle and (stainless adj steel) and (loadlock adj chamber) | USPAT | 2004/03/31 15:45 |
| - | 4 | PECVD and apparatus and chamber and insulator and (gas with ring) and susceptor and heater and wafer and sidewall and pump and (power adj source) and nozzle and (stainless adj steel) and (hold\$ with chamber) | USPAT | 2004/03/31 15:53 |

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|---|---|----------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------|-------|------------------|
| - | 0 | PECVD and apparatus and chamber and insulator and (gas with ring) and susceptor and heater and wafer and sidewall and pump and (power adj source) and nozzle and (stainless adj steel) and (holding adj chamber) | USPAT | 2004/03/31 15:49 |
| - | 0 | PECVD and apparatus and chamber and insulator and (gas with ring) and (susceptor with aluminum) and heater and wafer and sidewall and pump and (power adj source) and nozzle and (stainless adj steel) and (hold\$ with chamber) | USPAT | 2004/03/31 15:54 |
| - | 0 | PECVD and apparatus and chamber and (susceptor with (Al2O3)) and heater and wafer and sidewall and pump and (power adj source) and nozzle | USPAT | 2004/03/31 15:55 |